## Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

- 1-6. (Cancelled).
- 7. (Currently Amended) A semiconductor device, comprising:

a substrate including a plurality of holes and a surface over which an interconnecting pattern is formed, part of the interconnecting pattern being superposed over the holes;

a semiconductor chip disposed over another surface of the substrate and including a plurality of electrodes to be positioned over the holes; and

conductive members provided within the holes for electrically connecting the electrodes to the interconnecting pattern,

wherein a recognition hole is formed in the substrate at a position differing from the holes; and

wherein a recognition pattern is formed over the recognition hole on the side of a surface of the substrate including the interconnecting pattern.

- 8. (Currently Amended) The semiconductor device as defined in claim 7,

  wherein the recognition hole is formed in the substrate outside a mounting region for the semiconductor chip.
- 9. (Currently Amended) The semiconductor device as defined in claim 7,
   wherein the recognition pattern includes:

a first pattern extending in the X-axis direction of the two-dimensional coordinate system established on a surface of the substrate; and

a second pattern extending in the Y-axis direction.

10-12. (Cancelled).

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13.	(Currently Amended) A semiconductor device, comprising:
	a substrate including a plurality of holes and a surface over which an
interconnectin	g pattern is formed, part of the interconnecting pattern being superposed over
the holes;	
	a semiconductor chip disposed over another surface of the substrate and
including a pl	urality of electrodes to be positioned over the holes; and
	conductive members provided within the holes for electrically connecting the
electrodes to the interconnecting pattern,	
	wherein the conductive members are a plurality of layered bumps,
	wherein the bumps include first bumps formed on the electrodes and second
bumps formed on the first bumps, and	
	wherein the second bumps are formed of a metal which has a melting point
lower than the	melting point of the first bumps.
14.	(Currently Amended) The semiconductor device as defined in claim 13,
	wherein the first bumps are formed of gold.
15.	(Currently Amended) The semiconductor device as defined in claim 14,
	wherein-the second bumps are formed of solder.
16-33.	(Cancelled).